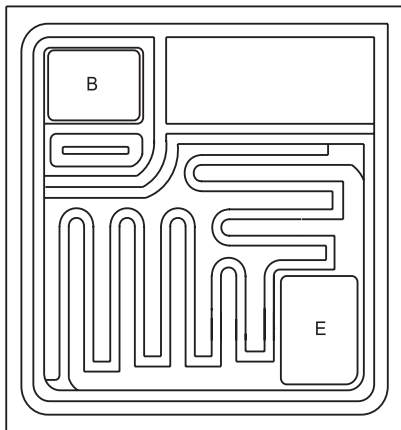


PROCESS DETAILS

Process	EPITAXIAL PLANAR
Die Size	27 x 27 MILS
Die Thickness	9.0 MILS
Base Bonding Pad Area	5.3 x 3.8 MILS
Emitter Bonding Pad Area	5.3 x 6.5 MILS
Top Side Metalization	Al - 30,000Å
Back Side Metalization	Au - 18,000Å

GEOMETRY



BACKSIDE COLLECTOR

R1

GROSS DIE PER 4 INCH WAFER

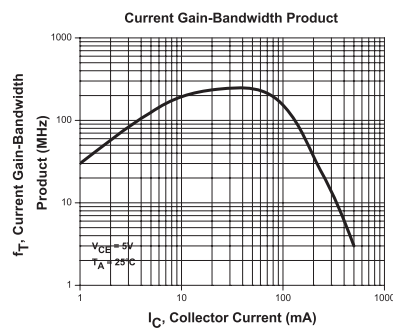
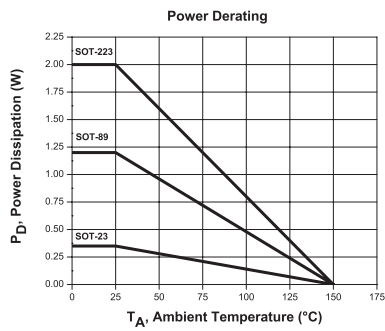
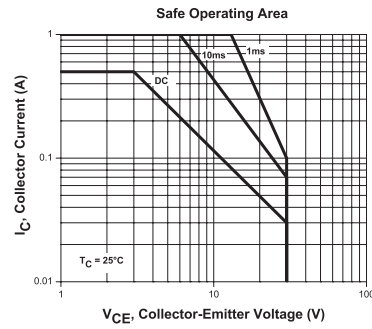
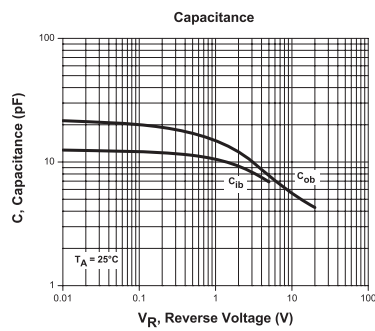
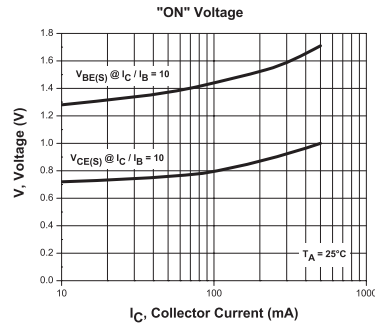
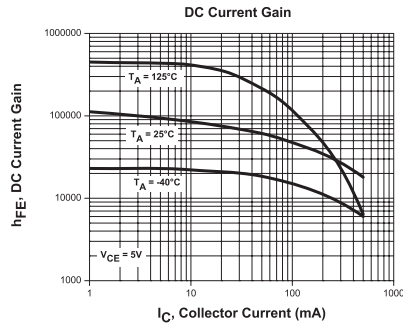
15,165

PRINCIPAL DEVICE TYPES

CMPTA63
CMPTA64
CXTA64
CZTA64
MPSA63
MPSA64

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R5 (8-October 2008)



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